AMENDMENTS TO THE SPECIFICATION:

Please replace the paragraph at Page 4, line 11, with the following:

The former developer having such a high pH has a problem, in addition to the handling problem, that an image area of a PS plate is easily damaged when the PS plate is developed. The latter developer has a problem that the contained silicate easily ~~gelates~~ gels and becomes insoluble due to the decrease of the pH of the developer during the developing process.

Please replace the paragraph at Page 11, line 10, with the following:

Examples of the monomer unit having a sulfonic acid group in the polymer compound of the intermediate layer include p-styrenesulfonic acid, 2-acrylamide-2-methylpropanesulfonic acid, ~~ehtylenesulfonic~~ ethylenesulfonic acid, 2-chloroethylenesulfonic acid, ethylenedisulfonic acid, 1-propene-1-sulfonic acid, 1-propene-2-sulfonic acid, 2-methyl-1,3-propenedisulfonic acid, 1-butene-1-sulfonic acid, 1-pentene-1-sulfonic acid, 1-hexene-1-sulfonic acid, 2-phenylethylenesulfonic acid, 1-methyl-2-phenylethylenesulfonic acid, 3-chloroallylsulfonic acid, allylsulfonic acid, 3-chloro-2-butenesulfonic acid, 3-chlorometaallylsulfonic acid, metaallylsulfonic acid, 3-methyl-2-butene-2-sulfonic acid, 3-phenylallylsulfonic acid, 3-phenylmetaallylsulfonic acid, 2-benzylallylsulfonic acid, 2-chloro-4-styrenesulfonic acid, vinyltoluenesulfonic acid, and α-methylstyrenesulfonic acid as well as alkali metal salt, ammonium salt and aqueous salt thereof. More preferably, at least one monomer unit comprising a sulfonic acid is

derived from at least one monomer selected from the group consisting of p-styrenesulfonic acid, 2-acrylamide-2-methylpropanesulfonic acid, ethylenesulfonic acid, alkali metal salt thereof, ammonium salt thereof, and aqueous amine salt thereof.

Please replace the paragraph at Page 11, line 27, with the following:

The polymer compound may be prepared by polymerizing one or more monomers described above or by copolymerizing one or more monomers described above with other monomers. Such other monomers may be any monomer that can be copolymerized with the monomer comprising a sulfonic acid group, but preferable examples thereof include alkyl acrylates (e.g., methyl acrylate, ethyl acrylate, n-propyl acrylate, isopropyl acrylate, n-butyl acrylate, isobutyl acrylate, n-amyl acrylate, isoamyl acrylate, n-hexyl acrylate, 2-ethylhexyl acrylate, n-octyl acrylate, n-decyl acrylate, 2-hydroxyethyl acrylate and the like), alkyl methacrylates (methyl methacrylate, ethyl methacrylate, n-propyl methacrylate, isopropyl methacrylate, n-butyl methacrylate, isobutyl methacrylate, n-amyl methacrylate, 2-ethylhexyl methacrylate, n-octyl methacrylate, n-decyl methacrylate, 2-hydroxyethyl methacrylate and the like), styrenes (styrene, o-methylstyrene, m-methylstyrene, p-methylstyrene, 2,4-dimethylstyrene, 2,5-dimethylstyrene, 3,4-dimethylstyrene, 3,5-dimethylstyrene, 2,4,5-trimethylstyrene, 2,4,6-trimethylstyrene, o-ethylstyrene, o-sec-butylstyrene, o-tert-butylstyrene, p-fluorostyrene, 2,5-difluorostyrene, o-chlorostyrene, m-chlorostyrene, p-chlorostyrene, 2,4-dichlorostyrene, 2,5-dichlorostyrene, 2,6-dichlorostyrene, 3,4-dichlorostyrene, p-bromostyrene,

p-cyanostyrene and the ~~likde~~ like), acrylonitrile, methacrylonitrile, acrylamide, N-sec-butylacrylamide, N-tert-butylacrylamide, N,N-dibutylacrylamide, N-tert-butylmethacrylamide, acrylic acid, methacrylic acid, vinyl acetate, and the like.

Please replace the paragraph at Page 13, line 24, with the following:

The coating solution for the intermediate layer may comprise suitable additives such as a pH ~~regulant~~ regulator, e.g., phosphoric acid, phosphorous acid, hydrochloric acid, and lower molecular organic sulfonic acid, and a wetting agent, e.g, saponin.

Please replace the paragraph at Page 16, line 7, with the following:

Other examples include ~~vinyluretane~~ vinylurethane compound comprising two or more polymerizable vinyl groups in a molecule, prepared by an addition reaction of a vinyl monomer having a hydroxyl group represented by the following formula (A) with a polyisocyanate compound having two or more isocyanate groups as disclosed in J.P. KOKOKU No. Sho 48-41708.

$CH_2=C(R^1)COOCH_2CH(R^2)OH$ (A)

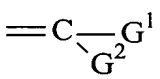
(wherein R^1 and R^2 each represents H or CH_3.)

Please replace the paragraph immediately following the formula on Page 21, with the following:

In the above formula, R^{17} and R^{18} each independently represents a hydrogen atom, alkyl group, substituted alkyl group, alkenyl group, substituted alkenyl group, alkynyl group, substituted alkynyl group, ~~alkoxycarobonyl~~ alkoxycarbonyl group, aryl group, substituted aryl group or aralkyl group. Z^6 represents an oxygen atom, sulfur atom, selenium atom, tellurium atom, alkyl or aryl-substituted nitrogen atom, or dialkyl-substituted carbon atom. Z^5 represents non-metallic atoms necessary to form a heterocyclic 5-membered ring containing a nitrogen atom. B^1 represents a substituted phenyl group, unsubstituted or substituted polynuclear aromatic ring, or unsubstituted or substituted heteroaromatic ring. B^2 represents a hydrogen atom, alkyl group, substituted alkyl group, aryl group, substituted aryl group, aralkyl group, alkoxyl group, alkylthio group, arylthio group, substituted amino group, acyl group, or ~~alkoxycarobonyl~~ alkoxycarbonyl group, or B^2 and B^1 may be linked together to form a ring.

Please replace the paragraph at Page 26, line 13, with the following:

Z^8 represents the following group:



wherein G^1 and G^2 may be the same or different and represent a hydrogen atom, cyano group, ~~alkoxycarobonyl~~ alkoxycarbonyl group, aryloxycarbonyl group, acyl group, arylcarbonyl group, alkylthio group, arylthio group, alkylsulfonyl group, arylsulfonyl group or fluorosulfonyl group, but G^1 and G^2 do not represent hydrogen atom

simultaneously. In addition, G^1 and G^2 may form a ring consisting of non-metallic atoms together with a carbon atom.

Please replace the paragraph at Page 36, line 9, with the following:

Further, the following other surfactants may be added to the developer used in the present invention; nonionic surfactants (e.g., polyoxyethylene alkyl esters such as polyoxyethylene stearate, sorbitan alkyl esters such as sorbitan ~~monolaulate~~ monolaurate, sorbitan monostearate, sorbitan distearate, sorbitan monooleate, sorbitan sesquioleate, and sorbitan trioleate, and monoglyceride alkyl esters such as glycerol monostearate, and glycerol monooleate); anionic surfactants (e.g., salts of alkylbenzenesulfonic acid such as sodium dodecylbenzenesulfonate, salts of alkylnaphthalenesulfonic acid such as sodium butylnaphthalenesulfonate, sodium pentylnaphthalenesulfonate, sodium hexylnaphthalenesulfonate, and sodium octylnaphthalenesulfonate, alkyl sulfates such as sodium laurylsulfate, salts of alkylsulfonic acid such as sodium dodecylsulfonate, and salts of sulfosuccinic acid ester such as sodium dilauryl sulfosuccinate); and amphoteric surfactants (e.g., alkylbetaine such as laurylbetaine and stearylbetaine, and amino acids), with the anionic surfactants such as alkylnaphthalenesulfonic acid salt being particularly preferred.

Please replace the paragraph at Page 39, line 7, with the following:

A 1S aluminum plate having a thickness of 0.30 mm was surface-grained with a No.8 nylon brush and a suspension of 800 mesh pumice stone in water and then sufficiently washed with water. After the plate was etched by immersing it in an aqueous solution of 10% sodium hydroxide for 60 seconds at 70°C, the plate was washed with running water. Then the plate was washed with 20% HNO_3 to neutralize it and washed with water. Then, an electrolytic graining of the plate was conducted in a 1% aqueous solution of nitric acid using a rectangle alternating continuous wave voltage with an anode electric amount of 300 coulomb/dm^2 under the condition of $V_A = 12.7V$. The roughness of the surface of the plate determined with an experimental device: ~~Surfcom~~ SURFCOM available from Tokyo ~~Seimitu~~ Seimitsu Co. Ltd., with a needle having a tip diameter of 2μm, was 0.45μm (Ra). The plate was then immersed in a 30% H_2SO_4 for 2 minutes at 55°C to desmut the surface. Then, the plate was anodized in a 20% aqueous solution of H_2SO_4 at 33°C by placing a cathode on the grained surface using an electric current density of 5A/dm^2 for 50 seconds to obtain a substrate having an anodized layer of which thickness was 2.7g/m^2.

Please replace the paragraph at Page 40, line 6, with the following:

(Photopolymerizable composition P-1)

Ethylenically unsaturated bond containing compound (A1)	1.5 part by weight
Linear organic polymer compound (polymer binder) (B1)	2.0 part by weight

Sensitizer (C1)	0.15 part by weight
Initiator of photopolymerization (D1)	0.2 part by weight
ε-Phthalocyanine (F1) dispersion	0.02 part by weight
Fluorine atom-containing nonionic surfactant, ~~Megafac~~ MEGAFAC F-177 (Dainippon Ink and Chemicals, Inc.)	0.03 part by weight
Methyl ethyl ketone	9.0 part by weight
Propyleneglycol monomethyl ether acetate	7.5 part by weight
Toluene	11.0 part by weight

Please replace the paragraph at Page 42, line 21, with the following:

(Developer 1)

Potassium hydroxide	0.15 g
Polyoxyethylene phenyl ether (n = 13)	5.0 g
~~Chelest~~ CHELEST 400 (chelating agent)	0.1 g
Water	94.75 g

Please replace Table 3 at Page 45, with the following:

Table 3

Developer 2		pH	conductivity
potassium hydroxide	0.15g	11.8	5 mS/cm
polyoxyethylene methylphenyl ether(n=10)	5.0g		
~~Chelest 400~~ CHELEST 400	0.1g		
water	94.75g		
Developer 3		pH	conductivity
potassium hydroxide	0.15g	11.7	6 mS/cm
polyoxyethylene naphthyl ether(n=10)	5.0g		
~~Chelest 400~~ CHELEST 400	0.1g		
water	94.75g		
Developer 4		pH	conductivity
potassium hydroxide	0.15g	11.9	6 mS/cm
triethanolamine	1.35g		
polyoxyethylene phenyl ether(n=12)	5.0g		
~~Chelest 400~~ CHELEST 400	0.1g		
water	93.4 g		
developer 5		pH	conductivity
potassium hydroxide	0.15g	12.3	8 mS/cm
polyoxyethylene naphthyl ether(n=10)	5.0g		
~~Anon LG~~ ANON LG	1.0g		
~~Chelest 400~~ CHELEST 400	0.1g		
p-t-butylbenzoic acid	1.0g		
water	92.3 g		